

Interference Search

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L7	185	((Ozone or O3 or "O.sub.3") same (CMP or polish\$6 or ground or grind\$6) same (surface or wafer or substrate or semiconductor)).clm.	US-PGPUB; USPAT	OR	ON	2007/01/05 12:05
L8	4	7 and (((adhes\$6 or diced or dicing or adher\$6 or scrib\$6 or cut\$6 or saw\$6 or separat\$6 or singula\$6) near20 (sheet or tape or pad or carrier)) same (polish\$6 or ground or grind\$6 or CMP) same (surface or wafer or substrate or semiconductor)).clm.)	US-PGPUB; USPAT	OR	ON	2007/01/05 12:07